

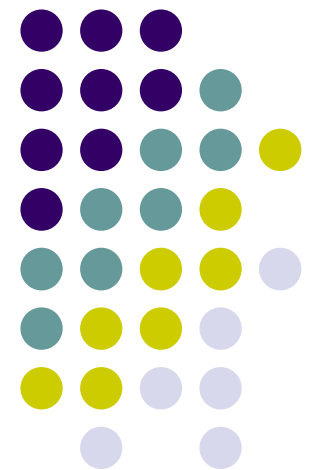
FPCCD Vertex Detector for ILC

Yasuhiro Sugimoto

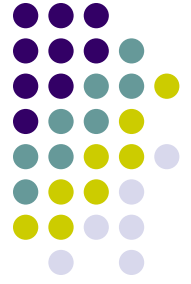
KEK

@TILC08

- ❑ Concept of FPCCD VTX
- ❑ FPCCD prototype
- ❑ VTX inner radius

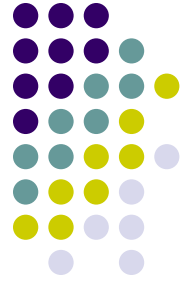


Basic concept



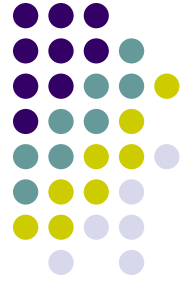
- Pair background at small R
 - ~5000 hits/cm²/train with B=3T and R=20mm
 - Pixel occupancy ~10% for 25μm pixel (several pixels are fired for one track hit)
 - In order to keep the occupancy small (<1%),
 - read out 20 times per train (1ms), or
 - 20 times finer pixel → Fine Pixel CCD (FPCCD)
- is necessary

Advantages of FPCCD VTX

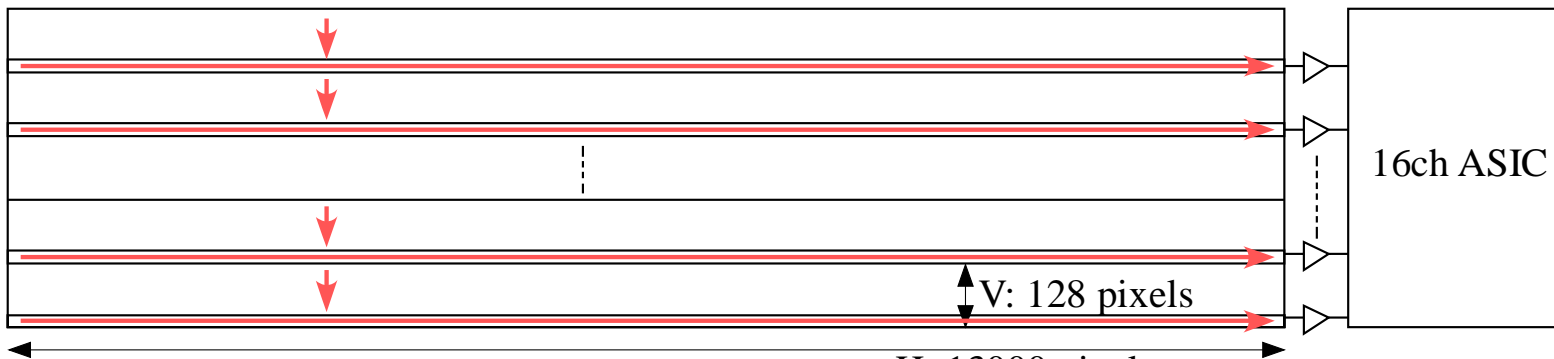


- Completely free from beam-induced RF noise (EMI)
- Excellent spatial resolution of $\sigma_x \sim 1.4\mu\text{m}$ even with digital readout
- Excellent two-track separation capability because of fine pixels and fully depleted epitaxial layer
- Capability of low-energy pair-background rejection by making use of hit-cluster shape
- Simple structure which enables large wafer size with high yield rate
- No heat source in the image area
- No need for very high readout speed

Schematic design



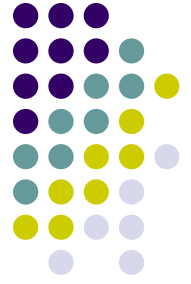
- Sensor and ASIC
 - $\sim 5\mu\text{m}$ square pixel
 - Multi-port readout to reduce readout time ($< 200\text{ms}$) with moderate readout speed ($\sim 10\text{Mpixels/s}$)
 - Small number of V-shift and large number of H-shift to reduce effect of radiation damage (CTI)
 - 15 – 20 μm thick fully depleted epitaxial layer



Size:
H: $5\mu\text{m} \times 13000 = 65\text{mm}$
V: $5\mu\text{m} \times 128 \times 16 = 10.24\text{mm}$

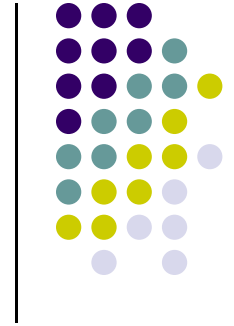
16ch Outputs
0.64mm pitch

R&D for FPCCD sensor

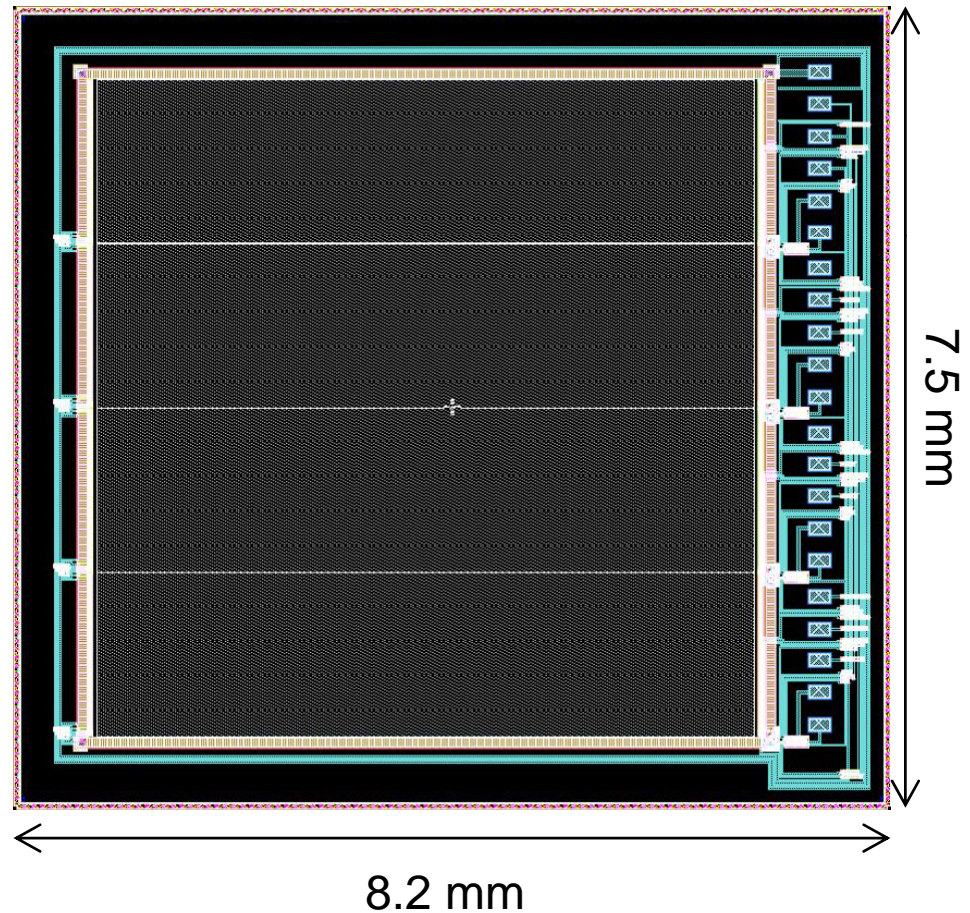


- Challenges of FPCCD
 1. Small pixel size $\sim 5 \mu\text{m}$
 2. Readout speed $> 10 \text{ MHz}$
 3. Noise < 50 electrons (preferably < 30 electrons)
 4. Power consumption $< 10 \text{ mW/ch}$
 5. Horizontal register (same size as pixel) in the image area
 6. Wafer thickness $\sim 50 \mu\text{m}$
 7. Multi-channel low power readout ASIC → Takubo's talk
- Prototype sensor in FY2007
 - Tackle issues 2, 3, 4, and 5

Prototype of FPCCD



- 12 μ m pixel size
- 512x512 pixels
- 6.1x6.1 mm² image area
- 4ch /chip
- 128(V)x512(H) pixels for each channel
- Several different designs of output amp
- Chips have been made and are being tested by HPK
- To be delivered in few weeks



Types of Prototype

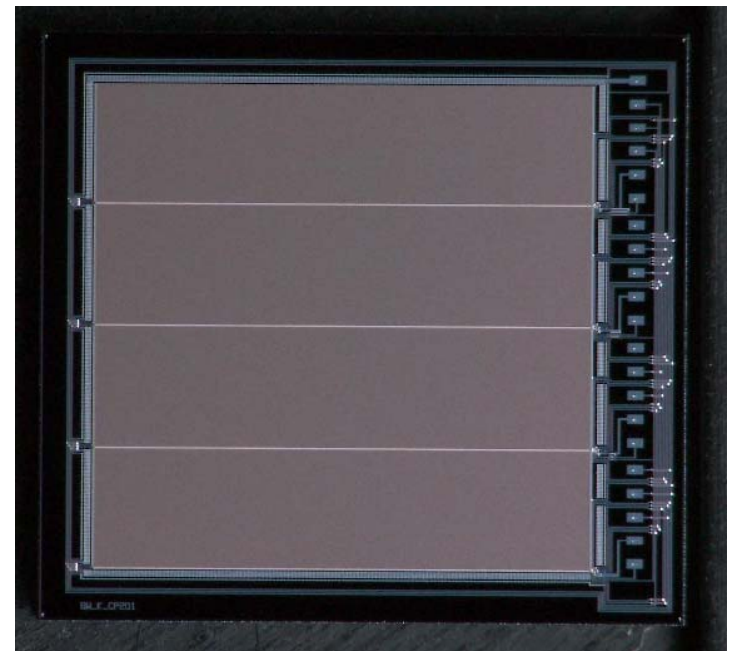
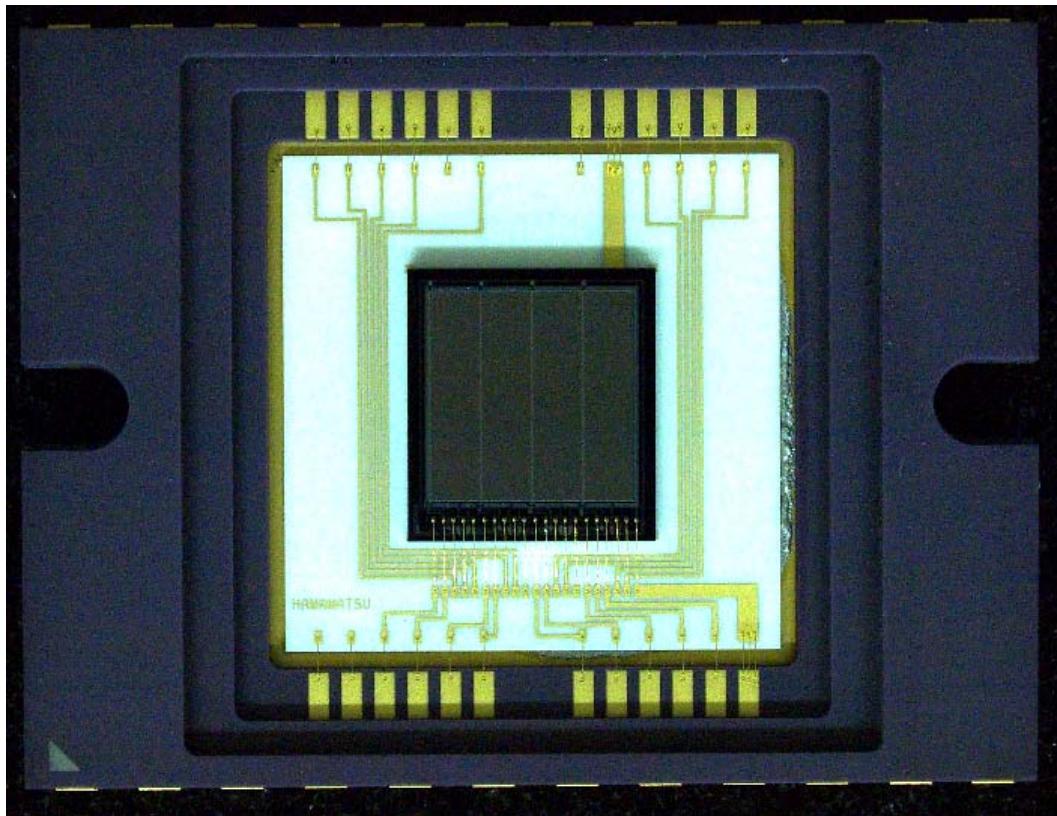


- Output amp: type A – H

		CP201	CP203	CP204	CP205
12umx512x127					
12umx512x 1	OS4	A	E	B	C
12umx512x127					
12umx512x 1	OS3	B	F	C	C
12umx512x127					
12umx512x 1	OS2	C	G	H	C
12umx512x127					
12umx512x 1	OS1	D	D	D	C

- Process / Device type
 - Wafer: epitaxial layer 24 / 15 μm
 - Gate SiO_2 for output Tr: standard (all) / thin (CP204, 205)
 - Device type: package / bare chip

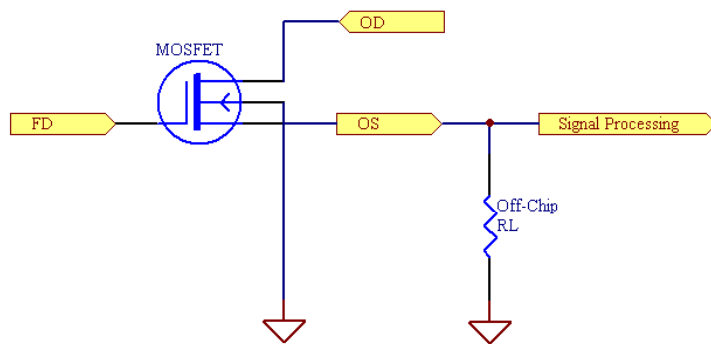
Packaged and bare chip



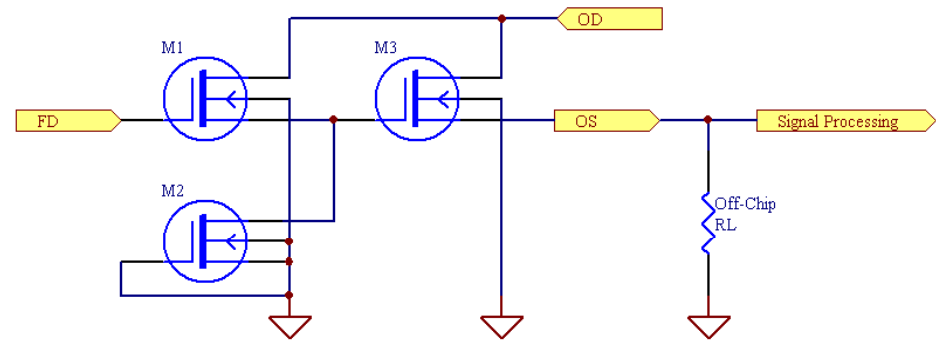
Output amp



- Type D

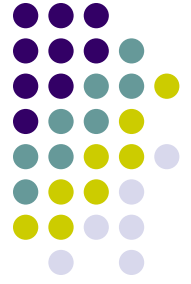


- Others



Type	M1	M2	M3
A	M1-Type1	M2-Type1	M3-Type1
B			M3-Type2
C			M3-Type3
E		M2-Type2	M3-Type2
F			M3-Type3
G			M3-Type4
H		M2-Type1	M3-Type4
Remark			Type1 > Type2 at drain current

Characteristics of Prototype



- Preliminary results given by HPK

Device type	Package		Bare chip	
Epi thickness (μm)	15	24	15	24
V-register gate capacitance (pF)	1600	550	1600	550
H-register gate capacitance (pF)	40	40	40	40
Output source capacitance (pF)	<4	<4	<2	<2

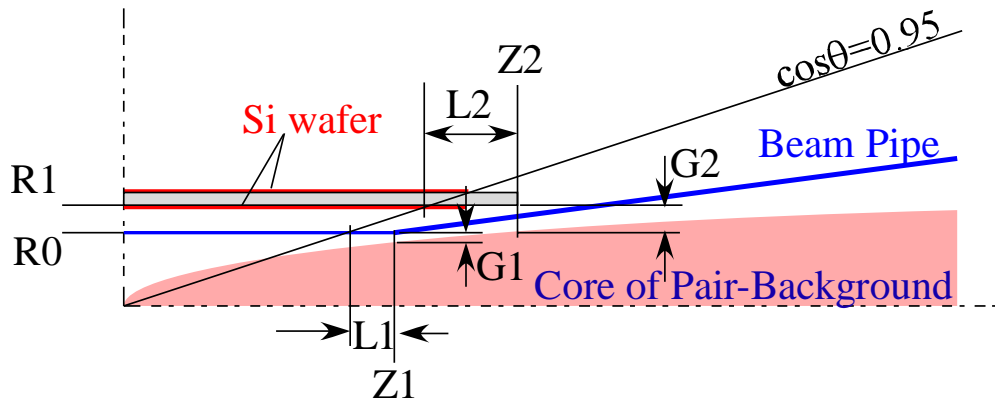
Amp type		A	B	C	E	F	G
Output gain ($\mu\text{V}/\text{e}$)	Epi:15 μm	5.4	5.3	5.2	6.9	6.2	5.6
	Epi:24 μm	5.8	5.3	5.0	6.6	5.9	5.4
Id (mA)	Epi:15 μm	1.57	1.55	1.50	1.28	1.22	1.14
	Epi:24 μm	1.48	1.44	1.38	1.15	1.09	0.99

$V_{\text{OD}}=10\text{V}$, $R_{\text{L}}=10\text{k}\Omega$, 10MHz, RT

Study on inner radius



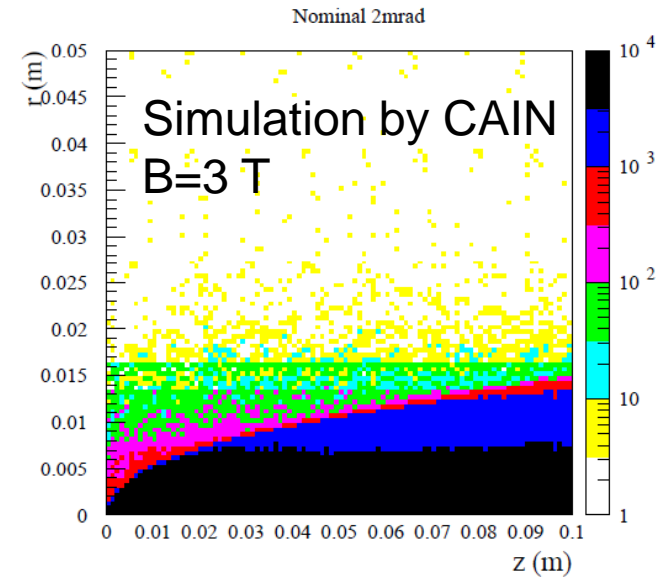
- Design criteria
 - Reasonable clearance between pair-background core and beam pipe, and between beam pipe and ladder



$G_1=2\text{mm}, G_2=4\text{mm}, L_1=5\text{mm}, L_2=20\text{mm}$

B (T)	E_{CM} (GeV)	Option	R_0 (mm)	R_1 (mm)
3	500	Nominal	13	17.5
3	500	Low P	17	22

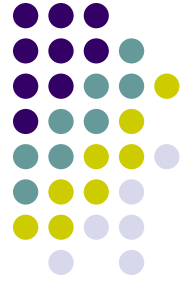
Strong dependence on machine parameters



(500GeV Nominal)

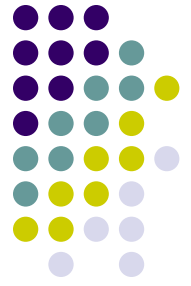
B (T)	R_0 (mm)	R_1 (mm)
3	13	17.5
3.5	12	16
4	11.5	15

Summary and outlook



- The first prototype FPCCDs have been made by HPK and will be delivered soon
 - Pixel size: 12 μ m
 - H-register same size as pixels in image area
 - 4ch/chip
 - Several types of output circuit
 - Two different epitaxial layer thickness (15 / 24 μ m)
 - Two different gate oxide thickness for output transistors
- Detailed study on the prototype FPCCDs will be done in FY2008
- Radius of innermost layer R_{in} of VTX was studied for 3, 3.5, and 4T magnetic field, and $R_{in}=17.5, 16,$ and 15 mm are proposed, respectively

Backup slide



Collaboration



- KEK
 - A. Miyamoto, K. Nakayoshi, Y. Sugimoto
- JAXA/ISAS
 - H. Ikeda
- Tohoku University
 - T. Nagamine, Y. Takubo, H. Yamamoto
- Tohoku Gakuin University
 - K. Abe

FPCCD VTX



- Vertex detector

- Two CCD layers make a ladder in order to make mini-vector of tracks and reject pair-background tracks
- 3 ladders make the vertex detector
- Operation at ~ -50 degrees
- Ladders are confined in a cryostat
- Angular coverage:
 - $|\cos\theta| < 0.95$ with inner 4 layers
 - $|\cos\theta| < 0.9$ with all 6 layers

